

List of Reference Symbols

100 Integrated circuit
101 Silicon substrate
102 Contact-making element
103 First field-effect transistor
104 Second field-effect transistor
105 Gate region
106 Gate region
200 First layout view of an integrated circuit
201 First field-effect transistor
202 Second field-effect transistor
203 Common gate line
203a First gate component
203b Second component
203c First course direction
203d Second course direction
203e Third course direction
203f Fourth course direction
204 Active region
204a First course direction
204b Second course direction
205 Active region
205a First course direction
205b Second course direction
206 First square contact-making element
207 Second square contact-making element
208 Third square contact-making element
300 Second layout view of an integrated circuit
301 First rectangular contact-making element
301a Third course direction
301b Fourth course direction
302 Second rectangular contact-making element
302a Third course direction
302b Fourth course direction
303 Third rectangular contact-making element
303a Third course direction
303b Fourth course direction
401 Lithography device

405 Silicon wafer
406a Processed chips
406b Unprocessed chips
406c Chip to be processed
407 Aligning optical arrangement
408 Reticle
409 Lens
410 Prealigning optical arrangement
411 Laser interferometer
412 Mirror area
413 xy table
414 Objective
415 Carrier element
440 Flow diagram
450 First method step
455 Second method step
460 Third method step
465 Fourth method step
470 Fifth method step
475 Sixth method step